



Dr. Taeho Shin

(ICD, Korea)

Dr. Taeho Shin is Vice President and Head of the Semiconductor Division at ICD Co., Ltd., where he leads the development and commercialization of advanced dry etching systems for next-generation semiconductor manufacturing. He has nearly 30 years of experience in plasma processing and dry etch technologies, with leadership roles spanning both the United States and Korea.

He began his career at Applied Materials in California as Technical Staff, contributing to the development and optimization of dry etcher hardware and processes. In 2007, he joined SEMES as Executive Director and Head of the Etch Business Division, overseeing the development of dielectric and conductor dry etchers as well as MOCVD systems.

Dr. Shin has served as an invited professor at Sungkyunkwan University, advising on advanced plasma technologies including ICP, Atomic Layer Etching, and magnetized plasma sources. He has also consulted for major semiconductor companies such as SK hynix and supported national equipment initiatives. Additionally, he founded Gateway Equipment & Total Technology, a startup focused on plasma etching solutions.

He holds over 20 international patents and has authored more than 15 technical papers in the field. Dr. Shin received his Ph.D. in Materials Engineering from Stevens Institute of Technology, U.S.A., and his B.S. and M.S. degrees in Nuclear Engineering from Hanyang University, Korea.